

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application

SC/Serial No.: SEE SCHEDULE A Filed:

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Title:

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PATENT APPLICATION

Customer No. 23910

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Tina M. Galdos

(Signature)

Signature Date: December 17, 2002

CHANGE OF ADDRESS

Commissioner for Patents Washington, DC 20231

Sir:

I am the attorney of record for the patents and patent applications listed on Schedule A attached hereto. Please be notified that my address has changed to the following:

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Please send all future correspondence concerning the patent and patent applications listed on

Schedule A to the above address.

12-17-02

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SCHEDULE A

LIST OF ISSUED PATENTS

Title	Filing Date	U.S. Serial No.	Issue Date	Patent No.	Old (BDSM) Attorney Docket No.	New Attorney Docket No.	
Null Test Fourier Domain Alignment Technique for Phase-Shifting Point Diffraction Interferometer	1/12/1999	09/229,449	8/29/2000	6,111,646	015780-024	LBLL-01024US0	<u> </u>
Phase-Shifting Point Diffration Interferometer Mask Designs	10/21/1998	09/176,617	10/23/2001	6,307,635	015780-025	LBLL-01025US0	
Phase-Shifting Point Diffraction Interferometer Grating Designs	10/21/1998	09/176,695	2/27/2001	6,195,169	015780-027	LBLL-01027US0	
Phas-Shifting Point Diffraction Interferometer Focus-Aid Enhanced Mask	7/26/1999	09/361,780	11/21/2000	6,151,115	015780-028	LBLL-01028US0	
Dual-Domain Point Diffraction Interferometer	4/27/1999	09/300,539	8/8/2000	6,100,978	015780-030	LBLL-01030US0	
In Situ Alignment System for Phase Shifting Point-diffraction Interferometry	6/2/1999	09/324,903	9/12/2000	6,118,535	015780-031	LBLL-01031US0	
Phase-Shifting Point Diffraction Interferometer Phase Grating Designs	10/14/1999	09/419,703	7/24/2001	6,266,147	015780-032	LBLL-01032US0	
Interferometric At-Wavelength Flare Characterization of EUV Optical System	7/28/2000	09/627,533	5/15/2001	6,233,056	015780-033	LBLL-01033US0	
Method of Fabricating Reflection-Mode EUV-Diffraction Elements	12/5/2000	09/730,970	5/21/2002	6,392,792	015780-039	LBLL-01039US0	—

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SCHEDULE A

LIST OF PENDING PATENT APPLICATIONS

-1					
	Title	Filing Date	U.S. Serial No.	Old (BDSM) Attorney Docket No.	New (FDML) Attorney Docket No.
	Method and Apparatus for Inspecting Reflection Masks for Defects	11/17/1998	09/193,198	015780-026	LBLL-01026US0
	System for Interferometric Distortion Measuremens That Define an Optical Path	5/11/2000	09/569,168	015780-029	LBLL-01029US0
ļ	Dual-Domain Lateral Shearing Interferometer	8/4/2000	09/632,631	015780-034	LBLL-01034US0
	Hybrid Shearing and Phase-Shifting Point Diffraction Interferometer	7/17/2000	09/617,719	015780-035	LBLL-01035US0
1	Method of Fabricating Reflection-Mode EUV Diffusers	4/30/2001	09/846,150	015780-040	LBLL-01040US0
	Apparatus for Generating Partially Coherent Radiation	8/30/2001	09/944,391	015780-041	LBLL-01041US0
i	A Holographic Illuminator for Synchrotron-Based Projection Lithography Systems	10/16/2001	09/981,500	015780-042	LBLL-01042US0
	Synchrotron-Based EUV Lithography Illuminator Simulator	6/5/2002	10/163,479	015780-043	LBLL-01043US0
	Diffractive Optical Element for Extreme Ultraviolet Wavefront Control	9/17/2001	09/956,160	015780-044	LBLL-01044US0